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(71)Applicant : EBARA YUJI RAITO KK

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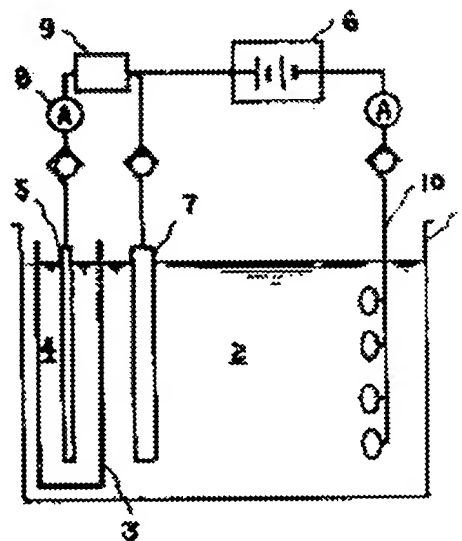
(72)Inventor : TSUJI HIDENORI
HATAKEYAMA YUKO
KAMIYA MASAOKI
ANDO SHIGEKAZU

(54) METHOD FOR ELECTROPLATING

(57)Abstract:

PURPOSE: To stabilize the composition of a plating bath and enable to operate for a long period by providing an insoluble auxiliary anode, in addition to a soluble anode, in an aqueous acid soln. via a cation exchange membrane in a plating tank, and flowing a part of current thereto for plating.

CONSTITUTION: In a plating tank 1, an insoluble auxiliary anode 5 delineated by a cation exchange membrane 3 is additionally provided, aside from a soluble anode 7, and an aqueous acid soln. is filled therein. A DC power source 6 is connected in series to the auxiliary anode 5 via a current controller 9 and an ammeter 8. The current corresponding to the difference in the current efficiencies of the soluble anode 7 and cathode 10 in the plating bath 2 is flowed to the auxiliary anode 5, whereby electroplating is accomplished. The rate of the current supply to the auxiliary anode 5 is controlled by the current controller 9 according to the fluctuations in the pH value of the plating bath 2. For example, titanium, platinum or the like is used for the auxiliary anode 5. Thereby, hydrogen ions may be supplied to the plating bath through the cation exchange membrane 3, and the increase in the pH and the metallic ion concn. of the plating bath 2 may be suppressed.



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